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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/755,717	01/05/2001	Lizhong Sun	AMAT/5538/CMP/CMP/RKK	5164

32588 7590 09/11/2002

APPLIED MATERIALS, INC.
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SANTA CLARA, CA 95050

EXAMINER

BROWN, CHARLOTTE A

ART UNIT	PAPER NUMBER
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1765

DATE MAILED: 09/11/2002

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Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.
09/755,717

Applicant(s)

Sun et al.

Examiner

First Last

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1234

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136 (a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on Jan 5, 2001
- 2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11; 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-67 is/are pending in the application.
- 4a) Of the above, claim(s) 1-26 is/are withdrawn from consideration.
- 5) ☐ Claim(s) is/are allowed.
- 6) ☒ Claim(s) 27-67 is/are rejected.
- 7) ☐ Claim(s) is/are objected to.
- 8) ☐ Claims are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on is/are a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
- 11) ☐ The proposed drawing correction filed on is: a) ☐ approved b) ☐ disapproved by the Examiner.
If approved, corrected drawings are required in reply to this Office action.
- 12) ☐ The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

- 13) ☐ Acknowledgement is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) ☐ All b) ☐ Some* c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. .
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
*See the attached detailed Office action for a list of the certified copies not received.
- 14) ☐ Acknowledgement is made of a claim for domestic priority under 35 U.S.C. § 119(e).
a) ☐ The translation of the foreign language provisional application has been received.
- 15) ☐ Acknowledgement is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892) 4) ☐ Interview Summary (PTO-413) Paper No(s).
2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948) 5) ☐ Notice of Informal Patent Application (PTO-152)
3) ☒ Information Disclosure Statement(s) (PTO-1449) Paper No(s). 3 6) ☐ Other:

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DETAILED ACTION

Election/Restriction

1. Restriction to one of the following inventions is required under 35 U.S.C. 121:
 - I. Claims 1-26, drawn to a composition for selective removal of tantalum, classified in class 252, subclass 79.1.
 - II. Claims 27-67, drawn to a method for selective removal of a tantalum layer, classified in class 438, subclass 692.
2. The inventions are distinct, each from the other because of the following reasons:

Inventions I and II are related as product and process of use. The inventions can be shown to be distinct if either or both of the following can be shown: (1) the process for using the product as claimed can be practiced with another materially different product or (2) the product as claimed can be used in a materially different process of using that product (MPEP § 806.05(h)). In the instant case product as claimed can be used in a materially different process of using that product such as etching the substrate in the presence of the composition to remove the tantalum layer.
3. Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for examination purposes as indicated is proper.

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4. During a telephone conversation with Eddie Song on August 7, 2002, a provisional election was made with traverse to prosecute the invention of Group II, claims 27-67.

Affirmation of this election must be made by applicant in replying to this Office action. Claims 1-26 are withdrawn from further consideration by the examiner, 37 CFR 1.142(b), as being drawn to a non-elected invention.

5. Applicant is reminded that upon the cancellation of claims to a non-elected invention, the inventorship must be amended in compliance with 37 CFR 1.48(b) if one or more of the currently named inventors is no longer an inventor of at least one claim remaining in the application. Any amendment of inventorship must be accompanied by a request under 37 CFR 1.48(b) and by the fee required under 37 CFR 1.17(I).

Claim Rejections - 35 USC § 103

6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

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7. Claims 27-67 are rejected under 35 U.S.C. 102(e) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Small (US 6,117,783).

Small discloses a chemical mechanical polishing composition and process. An intermetal dielectric layer is deposited over a substrate. A barrier layer composed of Ta, TaN, Ti, or TiN is deposited over a substrate. Copper metal is then deposited over the barrier layer. The copper metal, barrier metal, and dielectric layer is removed by chemical mechanical polishing. The polishing composition comprises hydroxylamine in DI water, which is a reducing agent, and hydrogen peroxide, which is an oxidizer. It is also possible to add chelating agents (Column 8, lines 36-45). A corrosion inhibitor such as gallic acid can also be added (Column 8, lines 59-65). If the chemical environment is too aggressive, the corrosion inhibitor that is absorbed on the surface will be dissociated from the surface, but will carry a metal ion with it. This reads on the applicant's limitation of the composition comprising ions from at least one transitional metal. A sufficient amount of selectively oxidizing and reducing compound is provided in the composition to produce a differential removal of the metal and a dielectric material (Column 5, lines 34-42). Therefore, this reads on the applicant's limitation of the polishing composition being conductive material layer selective. The chemical mechanical composition can have a pH from 2 to 12 (Column 3, lines 58-59).

Although Small does not teach that the polishing composition is barrier layer selective, he does teach that the composition uses a sufficient amount of a selectively oxidizing and reducing compound to produce a differential removal of the metal layer and the dielectric material. Since

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the barrier layer is also removed with the composition, it is inherent that the polishing composition is barrier layer selective.


8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. (US 6,313,039).

9. Any inquiry concerning this communication from the Examiner should be directed to Charlotte A. Brown whose telephone number is 703-305-0727. The Examiner can normally be reached during the hours of 9:00AM to 6:30PM.

The fax phone numbers where this application or proceeding is assigned are 703-872-9310 for regular communications and 703-872-9311 for After Final communications.

CAB

September 5, 2002


BENJAMIN L. UTECH
SUPERVISORY PATENT EXAMINER
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